

HCMOS STANDARD CELLS

PRELIMINARY DATA

FEATURES

- 0.5 micron triple layer metal HCMOS5S process featuring retrograde well technology, low resistance salicided active areas, polysilicide gates and thin metal oxide.
- 3.3 V optimized transistor with 5 V I/O interface capability
- 2 - input NAND delay of 210 ps (typ) with fanout = 2.
- Broad I/O functionality including LVCMOS, LVTTTL, GTL, PECL, and LVDS.
- High drive I/O; capability of sinking up to 48 mA with slew rate control, current spike suppression and impedance matching.
- Generators to support SPRAM, DPRAM, ROM and MULT with BIST options.
- Extensive embedded function library including DSP and ST micros, popular third party micros and Synopsys synthetic libraries.
- Fully independent power and ground configurations for inputs, core and outputs.
- I/O ring capability up to 800 pads.
- Output buffers capable of driving ISA, EISA, PCI, MCA, and SCSI interface levels.
- Active pull up and pull down devices.
- Buskeeper I/O functions.
- Oscillators for wide frequency spectrum.
- Broad range of 300 SSI cells.
- Low Power / Low Drive library subset.
- Design For Test includes IEEE 1149.1 JTAG Boundary Scan architecture built in.
- Cadence and Mentor based design system with interfaces from multiple workstations.
- Broad ceramic and plastic package range.
- Latchup trigger current > +/- 500 mA. ESD protection > +/- 4000 volts.

Table 1 Module Generator Library

Cell	Description
SPRAM	256K bits max 16K word max 64 bit max Zero static current Tristate outputs
DPRAM	128K bits max 8K word max 64 bit max Zero static current Tristate outputs
ROM	2M bits max 32K word max 64 bit max Diffusion programmable Tristate outputs
MULT	Parallel asynchronous operation 2's complement product 6 to 64 bits for both inputs Ripple Carry or Fast Carry Look Ahead

CB35000 SERIES

GENERAL DESCRIPTION

The CB35000 standard cell series uses a high performance, low voltage, triple level metal, HCMOS5S 0.5 micron process to achieve sub-nanosecond internal speeds while offering very low power dissipation and high noise immunity.

With an average gate density of 5500 gates/mm², the CB35000 family allows the design of highly complex devices. The potential available gate count ranges above 1.5 Million equivalent gates. Devices can operate over a V_{dd} voltage range of 2.7 to 3.6 volts.

The I/O count for this array family ranges to over 600 signals and 800 pins dependent upon the package technology utilized. A Sea of I/O approach has been followed to give a solution to

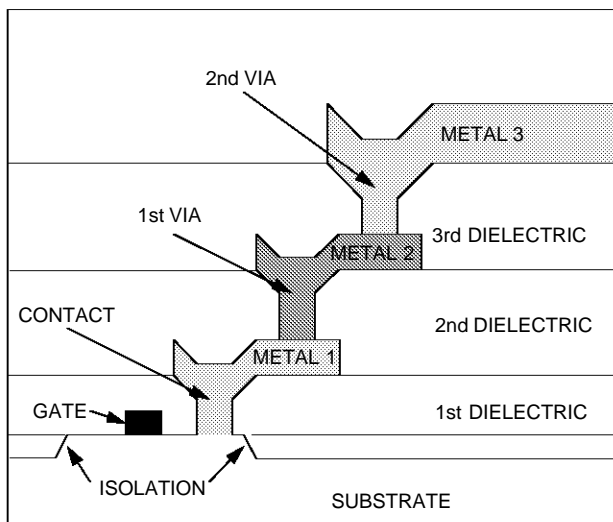
today's problems of drive levels and specialized interface standards. The technology does not utilize a set bond pad spacing but allows for pad spacings from 80 microns upwards. The I/O is fully compatible with that of the ISB35000 Structured Array family.

The I/O can be configured for circuits ranging from low voltage CMOS and TTL to 350 mHz plus low swing differential circuits. Standards like GTL, SCSI-2, 3.3 Volt PCI, CTI, and a limited set of 5.0 Volt interfaces are currently being addressed. A specialized set of impedance matched transmission line driver LVTTTL type circuits are also available with 25, 35, 45, and 55 Ohm output impedance. These buffers sacrifice direct current capabilities for matching positive and negative voltage and current waveforms.

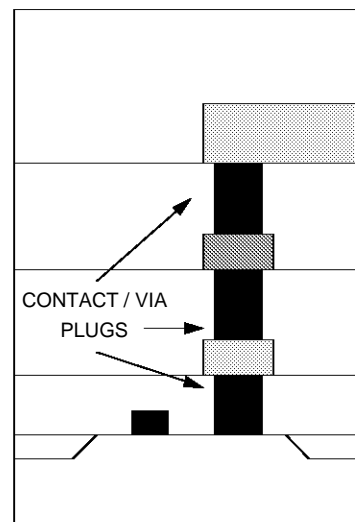
Figure 1

Advantages of stacked contacts and vias

CONVENTIONAL VIA LAYOUT



STACKED VIA LAYOUT



AREA SAVINGS UP TO 20% FOR RANDOM LOGIC

SIMPLIFIED ROUTING AND DESIGN RULE CHECKING

LIBRARY OVERVIEW

The design of the CB35000 family has been optimized to allow extremely high density, high speed and low power designs. For these reasons a wide range of cells with different ranges of driving capability are available in the library.

The library cells have been optimized in term of functional and electrical parameters in order to have:

- Good balancing
- Maximum speed
- Optimum Threshold voltage
- Symmetric Vdd/Vss Noise margin
- Minimum Power-Speed figure

Surrounding the core are configurational specialized transistors forming a Sea of I/O giving a high degree of flexibility to the system designer.

The geometrical aspect of the cells was configured to allow extremely dense design, fully

exploiting the features of the Place and Route tool in terms of horizontal and vertical routing grids. For Place and Route, three levels of metal are utilized. Intracell and intercell wiring are limited to first metal, with second and third metal levels dedicated to interconnect wiring and power distribution. Each cell gives the possibility to use 10 horizontal wiring channels using third metal. With the horizontal grid unit being the same as the Metal 2 minimum contacted pitch, the vertical wiring can be done on every grid point, without limitation.

TECHNOLOGY OVERVIEW

A major feature of the HCMOS5S process is salicided active areas. This results in source drain areas that are of one to two ohms resistance as opposed to the hundreds or thousands of ohms of source drain resistance in previous technologies. This very low resistance is one reason that very low transistor widths could be utilized in the cell design since drive is not lost due to source drain resistance. This use of low width transistors results in lower capacitance loading of the gates due to the smaller areas utilized. Low resistance, low capacitance, and small gates results in low power usage for inverters as compared to previous technologies. The reduction in power consumption allows the usage of salicided active stripes to distribute power internally to the simple cell, replacing, in some cases, the usage of the first metal layer. This saves silicon area by allowing greater density, permeability and routability of the cells resulting in greater overall circuit density.

The standard power distributions are Internal Vdd and Vss, serving the internal cells and the prebuffer sections of the I/O, External Vdd and Vss serving the output transistors only, and Receiver Vdd and Vss serving the first stages of the receiver cells. Optional distributions for 5.0V interface, GTL, CTL, and other standards can be utilized as necessary.

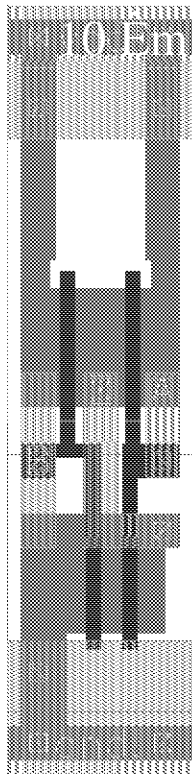


Figure 2. ND2 Core Cell

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LIBRARY

The following section details the elements which make up the CB35000 Series library. The elements are organized into three categories:

1. Macrocell library with Input, Output, Bidirectional Buffers including JTAG macrocells and Core cells.
2. Macrofunctions
3. Module generators.

I/O BUFFERS

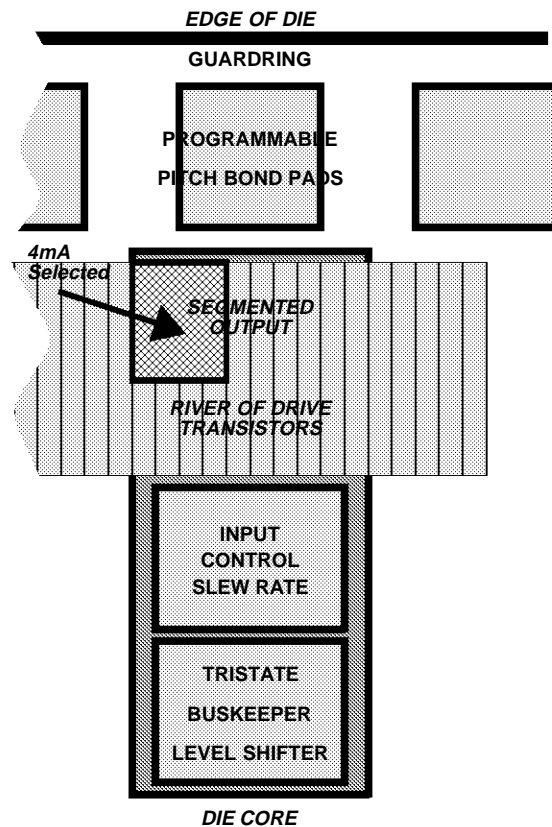
CB35000 technology does not utilize a standard type I/O cell but is a leader in the emerging Sea of I/O approach to handling the chip interface problem. This approach starts at the bond pad area of the I/O where the pad size and pitch is not determined until the customer's choice of packaging, signal interface standards and I/O count is considered. Wire bond pad spacings for 80 micron centres are available where large signal counts are most important.

Pad spacing can be increased incrementally. It is expected that most designs will use 100 micron spacings or above. It is also possible to use different spacings for different width output sections when needed within the same device.

Along with the variable bond pad spacing the I/O output transistor section does not have a fixed width. Previous technologies utilized a design approach where the desired full function buffer was designed for a maximum current taking one pad location with the usual current in the range of twenty four milliamps. The approach followed in CB35000 is to have identical twenty five micron wide output transistor slices stepped around the die. Each slice contains one set of protection diodes to the external power rails and eight P and eight N transistors. The transistors are specifically laid out and selectively non salicided for ESD protection and latch up prevention. These slices are paralleled to meet the current needs of the user, for example, to construct a 24mA sink and 12mA source LVTTL buffer, a number of slices would be used. The next group of devices that makes up the I/O circuits is again

a 25u wide slice of specialized transistors that are utilized to form the slew rate control sections of the I/O. Each of these slices has circuits to control the switching of up to two sections of P and N output transistors. These sections are of course created from the output transistor slice above the slew rate section and can be connected as desired by the designer. Many configurations of circuits can be created to supply the desired results with slew rate slices paralleled with multiple output sections. A further function of the I/O circuits is current spike suppression during switching of the I/O transistors. The logic utilized causes the conducting transistors to turn off before the opposing set of transistors turn on.

Figure 3
IO Buffer Technology



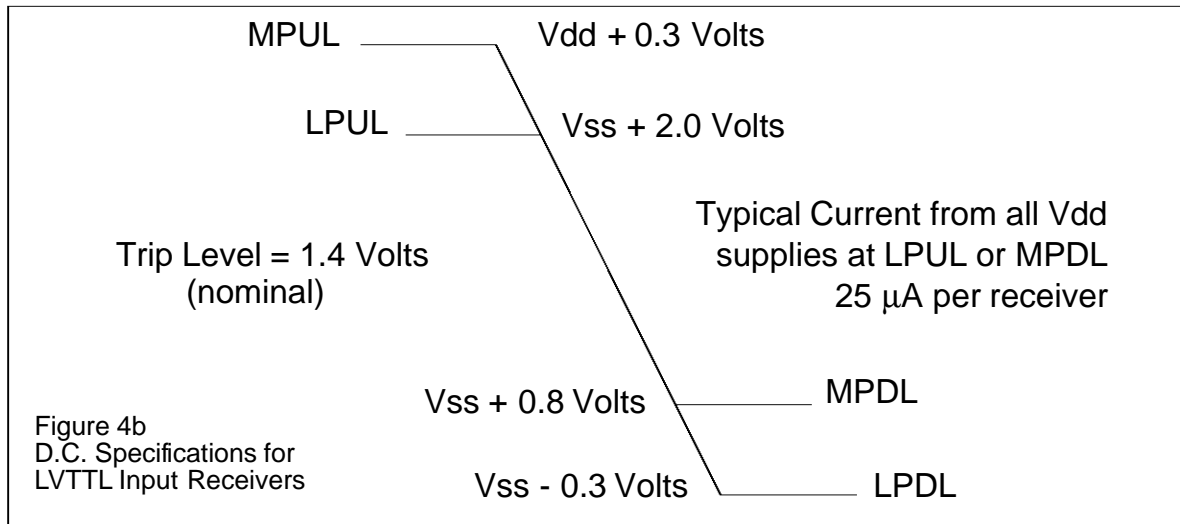
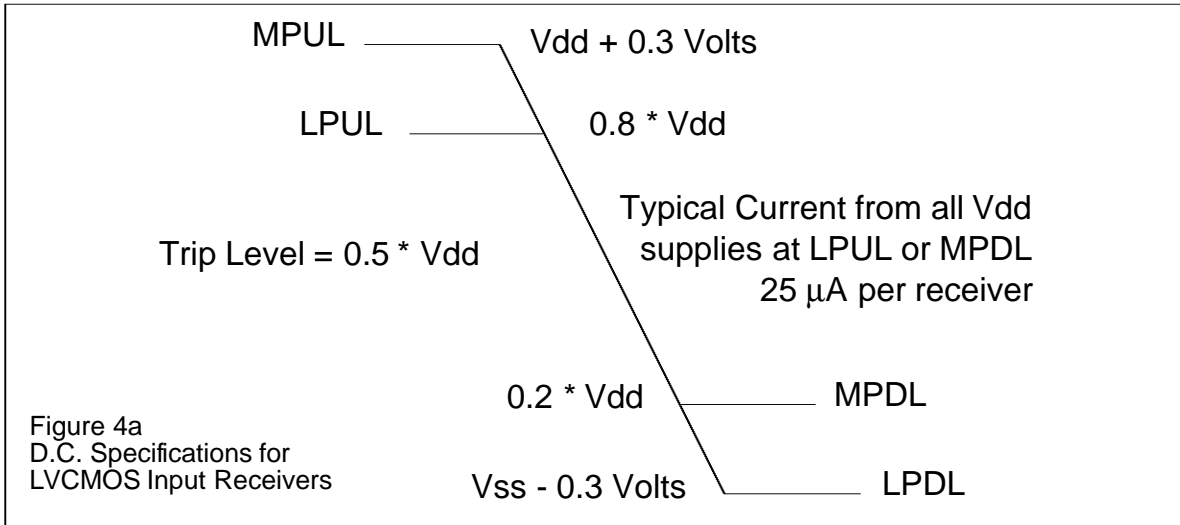


Table 2 I/O Drive Capacity for LVC MOS and LVTTL Slew Rate Buffers

Current Drive (mA)	Maximum Capacitance (pF)
2.0	50
4.0	100
8.0	200
12.0	300
16.0	400
24.0	800

Table 3 I/O Drive Capacity for LVC MOS and LVTTL Non Slew Rate Buffers

Current Drive (mA)	Maximum Capacitance (pF)
2.0	50
4.0	100
8.0	200
12.0	300
16.0	400
24.0	800

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Table 4 Temperature (Junction) and Voltage Multipliers

Temperature °C	K_T
-55	0.77
-40	0.83
25	1.00
70	1.13
85	1.17
125	1.27
V_{DD}	K_V
2.7	1.20
3.0	1.11
3.3	1.00
3.6	0.94

Inside the slew rate sections the next slices of specialized designed components step on a 50 micron wide pattern. The first of these 50 micron wide sections is utilized for predriver circuits; these include specialized built in test functions for the I/O. The predriver of course interfaces the core signals controlling tristate and switching functions with the slew rate and output transistor sections but it also allows all Output Buffers to be driven high, low or put into tristate regardless of the state of the internal logic greatly simplifying parametric testing of the part and also assisting customers who wish to use this feature during board testing. Note that all output buffers can be tristated by this function including buffers that normally do not tristate. This test function also turns off all pull up or down devices and shuts down all differential receivers and converts them into standard CMOS receivers. Inside the predriver is a section of specialized transistors used to create the receiver functions. This section includes specialized non salicide protection resistor diodes to further protect the gates of the receiver devices from ESD and latch up. Also present in this section are devices that can be utilized to form various parameterisable pull up, pull down and buskeeper functions. A full set of standard receivers with pull up and pull

down devices is present in the library. The technologies supported match the output buffer capabilities and include, LVCMOS, LVTTTL, GTL, CTL, Differential, etc. and a five volt interface capability.

All pads except the sixteen corner pads can be configured as power or I/O pads. The configured power pads are known as placeable pads and have an associated current handling capability. Their placement is dependent on the types of output buffers used in the design. For rules governing the placement of pads, please contact your local SGS-THOMSON design centre.

CORE LOGIC

The propagation delays shown in the CB35000 data book are given for nominal processing, 3.3V operation, and 25 C temperature conditions.

However there are additional factors that affect the delay characteristics of the macrocells. These include loading due to fanout and interconnect routing, voltage supply, junction temperature of the device, processing tolerance and input signal transition time. Prior to physical layout, the design system can estimate the delays associated with any critical path. The impact of the placement and routing can be accurately RC back annotated from the layout for final simulations of critical timing. The effects of junction temperature, (K_T) and voltage supply (K_V) on the delay numbers are summarized in Table 4. A third factor, is associated with process variation. This multiplier has a minimum of 0.8 and a maximum of 1.2.

MACROCELLS AND MACROFUNCTIONS

The CB35000 series has internal macrocells that are robust in variety and performance. The cell selection has been driven by the need of Synthesis and HDL based design techniques. This offering is rich in buffers, complex combinatorial cells and multi power drive cells, which allow the Synthesis tool to create a netlist compatible with the requirements of Place and Route tools.

Macrofunctions are a series of soft-macros facilitating quick capture of large functional blocks and are available for such functions as counters,

Table 5 Module Generator Library

Cell	Description
SPRAM	256K bits max 16K word max 64 bit max Zero static current, Tristate outputs
DPRAM	128K bits max 8K word max 64 bit max Zero static current, Tristate outputs
ROM	2M bits max 32K word max 64 bit max Diffusion programmable, Tristate outputs
MULT	Parallel asynchronous operation 2's complement product 6 to 64 bits for both inputs Ripple Carry or Fast Carry Look Ahead

shift register and adders. Macrofunctions are implemented at layout by utilizing macrocells and interconnecting to create the logic function.

MODULE GENERATORS

A series of module generators using compiled cell generation techniques, are available to support a range of megacells. These modules enable the designer to choose individual parameters in order to create a compiled cell, which meets the specific application requirements. These include single port RAM, dual port RAM, ROM and MULT. The compiled cell generators construct custom cells, which are implemented using a special leaf cell technique, ensuring predictable layout and accurate module characteristics. In choosing megacells the designer can consider the trade-offs between speed and area to generate a fully customized cell which meets their specific device requirements. These megacell generators are complemented by a group of application specific embedded megacells. These allow access to technologies that have been hitherto the domain of standard products. Examples include mixed mode cells for graphics, DAC/ADC's (4-9 bit), PLL applications, and Digital Signal Processor functions for cellular comms, fax and high-speed modem. which initially consist of a Triple 8-bit DAC, Graphics RAM, Clock Multiplier PLL and Frequency Synthesis PLL.

100 Mbps serial transputer links coupled with large and fast memory can be used for pipelining, caching and synchro circuits in modern RISC computing architectures. Viterbi and Reed Solomon cores aim at the HDTV and satellite transmission markets. To support telecom needs for CCITT standard applications, ADPCM cells supporting CT2 protocol have been developed.

DESIGN FOR TESTABILITY

The time and cost for ASIC testing increases exponentially as the complexity and size of the ASIC grows. Using a design for testability methodology allows large, more complex ASICs to be efficiently and economically tested.

CB35000 supports the JTAG boundary Scan and both edge and level sensitive scan design techniques by providing the necessary macrocells. Scan testing aids device testability by permitting access to internal nodes without requiring a separate external connection for each node accessed. Testability is assured at device level with the close coupling of LSSD latch elements, Automatic Test Pattern Generation (ATPG) and high pattern depth tester architecture. BIST options for memory generators are also available.

At system level, SGS-THOMSON fully supports IEEE 1149.1, and the I/O structure utilized in this family is completely compatible. Several types of

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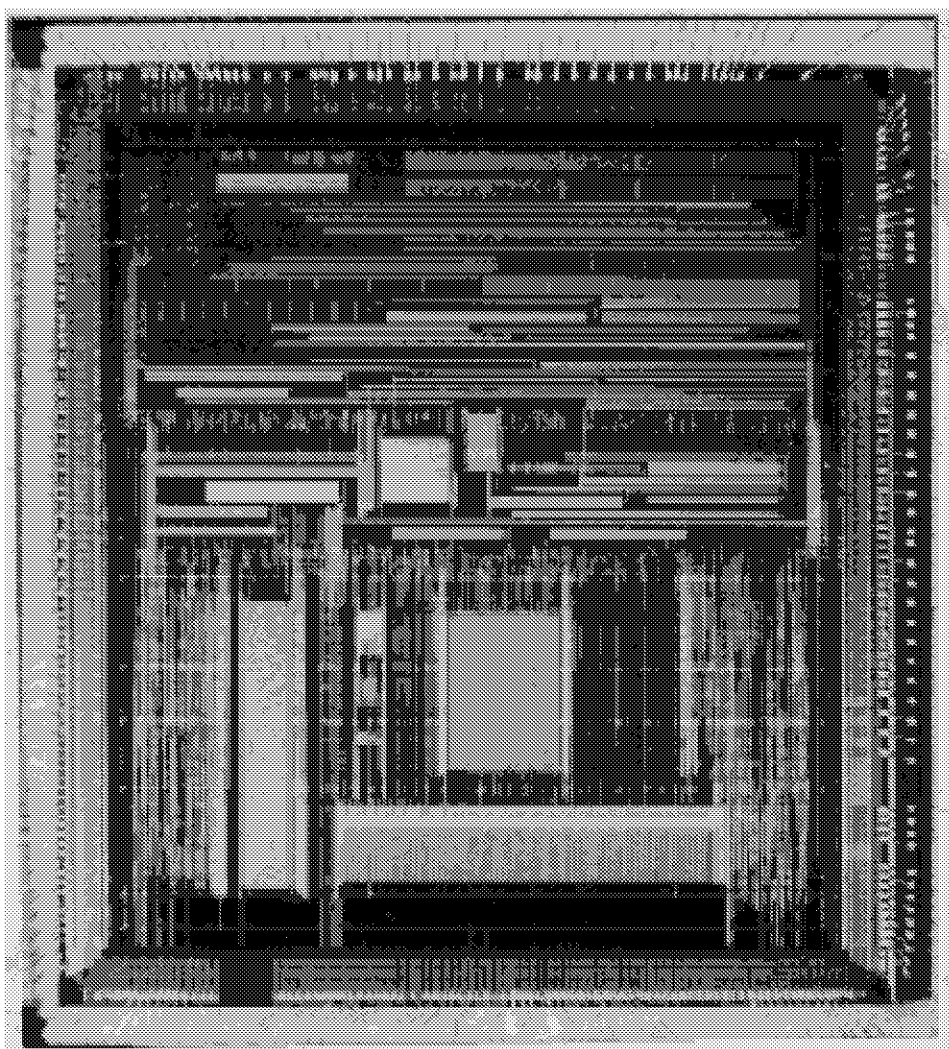
core scan cells are provided in the CB35000 Series library. Examples include FDxS/FJKxS cells which are edge sensitive and LSxx cells which are true LSSD cells. Non-overlapping clock generator macros are also available.

EVALUATION DEVICE

An evaluation device is used to demonstrate the performance of the CB35000 series as well as verify the effectiveness of the design system. The device has path delays, latches, a host of macrocells and memory functions which were

used to verify the simulated characteristics that are supplied in the data book. Characterization of the path delays including interconnect shows typical delays of 210 ps for a 2 input NAND with receivers/drivers operating at frequencies of 200 MHz. The evaluation device is available in a 208 pin plastic quad flat pack.

Figure 5
Evaluation Device



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PACKAGE AVAILABILITY

The CB35000 Series is designed to be compatible with QFP, BGA and SBC package types, in addition to the more traditional types found.

The options include Plastic Leaded Chip Carriers (PLCC) from 28 to 84 pins, while the Metric Quad Flat Pack (xQFP) offering ranges up to 208 pins. Both high performance and high power variants are available as well as the TQFP thin types.

Ball Grid Array (BGA) packages are available from 160 to 500 pins and SBC types allow the pin count to reach the area of 1000 pins. Pin counts for through board mounting (PGA) range up to 480.

The diversity in pin count and package style gives the designer the opportunity to find the best compromise for system size, cost and performance requirements.

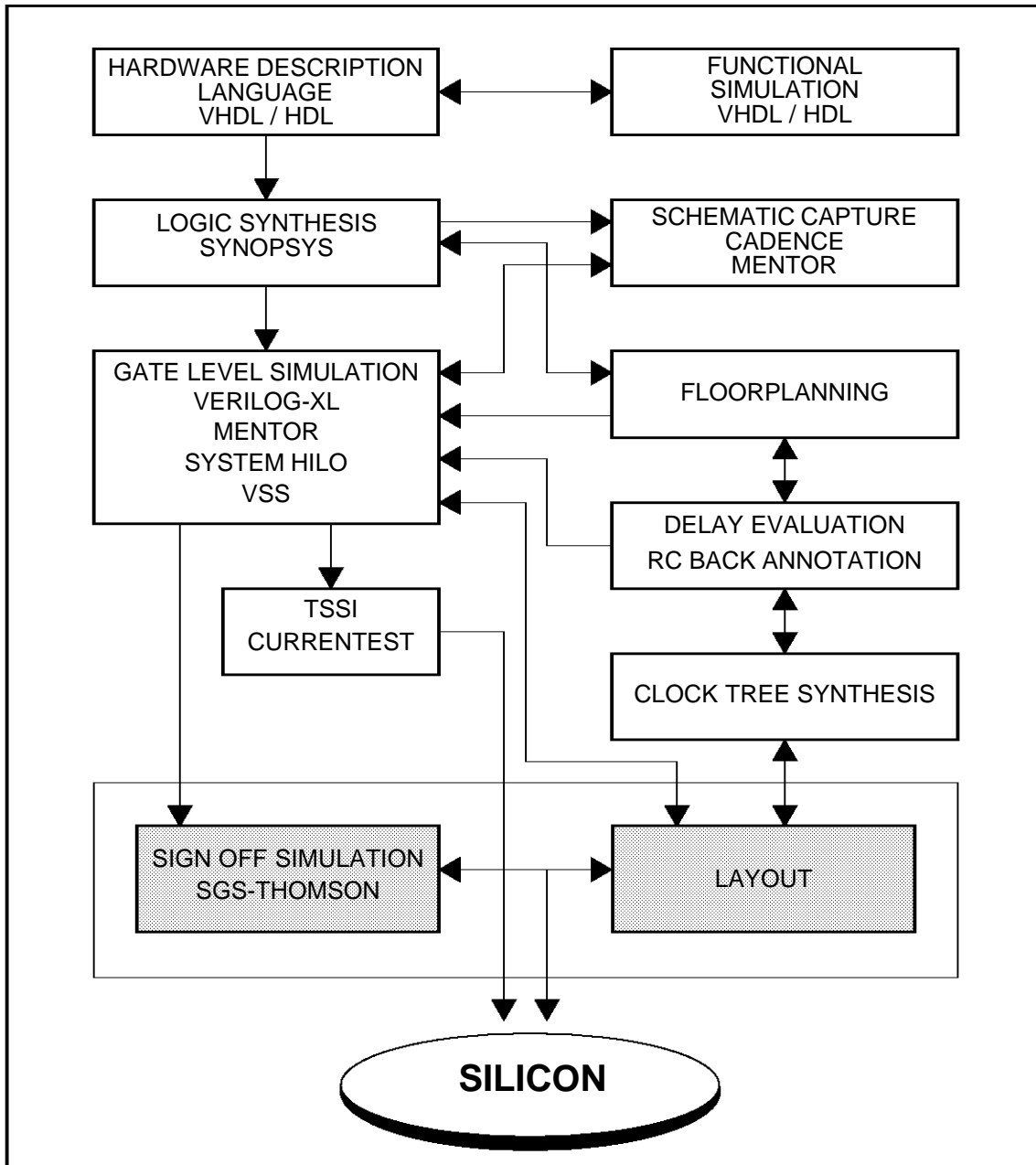
All packages for the military market are hermetically sealed to meet MIL-STD-883 Method. Prototypes are developed in ceramic packages for fast turnaround evaluation.

Figure 6
Packaging Capability

NUMBER OF LEADS (Pins)	PACKAGE NAME					
	PQFP	TQFP	BGA	PLCC	CPGA	POWER PQFP Slug/Spreader
20				○		
28				○		
44	○			○		
64	○	○				
68				○	○	
80	○	○				
84				○	○	
100	○	○			○	
120	○				○	○
128	○					○
144	○	○			○	○
160	○					○
176		○				
180					○	
208	○				○	○
224					○	
225			○			
256			○			
257					○	
304						
313			★		★	
400			★		★	
480			★		★	

- Packages in Production
- ★ Packages in Development

Figure 8
SGS-THOMSON Design Flow



CB35000 SERIES

Table 6 Absolute Maximum Ratings (note1)

Supply Voltage, Vdd	-0.5 V to +6.0 V
Input or Output Voltage	-0.5 V to (Vdd + 0.5V)
DC Forward Bias Current, Input or Output	-24mA source, +24mA sink
Storage Temperature Ceramic	-65 to 150 degrees Centigrade
Storage Temperature Plastic	-40 to 125 degrees Centigrade

Note 1. Referenced to Vss. Stresses above those listed under “absolute Maximum Ratings” may cause permanent damage to the device. This is a stress rating only and functional operation of the device at these or any other conditions above those indicated in the operation sections of this specification is not implied. Exposure to absolute maximum rating conditions for extended periods may affect the device reliability.

Table 7 Recommended DC Operating Conditions

Normal Operating Supply Voltage Vdd (note 1)	3.3 V +/- 10% (3.0 V to 3.6 V)
Extended Operating Supply Voltage Vdd (notes 1,2)	3.3 V + 0.3V/-0.6V (2.7V to 3.6V)
Operating Ambient Temperature	
Commercial (note 3)	0 to 70 degrees Centigrade
Industrial (note 3)	-40 to +85 degrees Centigrade
Military (note 4)	-55 to +125 degrees Centigrade

Note 1. Commercial, Industrial, and Military Conditions

Note 2. Low Voltage TTL Circuits are NOT functional to specifications below 3.0 Volts

Note 3. All circuits will operate to full specifications with a Vdd of 3.0V to 3.6V and a junction temperature of -40 to +125 degrees centigrade. These junction temperatures are compatible with the Commercial and Industrial Temperature Ranges.

Note 4. All circuits will be functional from -55 to +150 degrees centigrade junction temperature (military Ambient Temperature Range) but will not necessary operate to published specifications. Only circuits specified as operational to extended temperature range may be used when operating to Military temperature conditions.

Table 8 Special Voltages (Vcc) Operating Conditions

FVI (Five Volt Interface) Supply Voltage (notes 1,2)	5.0V +/- 10% (4.5 V to 5.5 V)
GTL (Gunning Transistor Logic) Supply Voltage (notes 1, 3)	1.2V +/- 5% (1.14 V to 1.26 V)
CTT (Center Tap Terminated) Supply Voltage (notes 1,4)	1.5V +/- 10% (1.35 V to 1.65 V)

Note 1. Commercial, and Industrial Use Only -40 +85 degrees Centigrade

Note 2. I/O Circuits Only takes Special External Power Distribution and May NOT be mixed with GTL or CTL circuits on any one side of the die. Only a very limited buffer set is available.

Note 3. I/O Circuits Only takes Special External Power Distribution and May NOT be mixed with FVI or CTL circuits on any one side of the die. Only a very limited buffer set is available.

Note 4. I/O Circuits Only takes Special External Power Distribution and May NOT be mixed with FVI or GTL circuits on any one side of the die. Only a very limited buffer set is available.

Table 9 LVTTTL Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Vil	Low Level Input Voltage				0.8	Volts	2,3
Vih	High Level Input Voltage		2.0			Volts	2,3
Vol	Low Level Output Voltage	Iol = Rated Buffer Current		0.2	0.4	Volts	2,3,4
Voh	High Level Output Voltage	Ioh = Rated Buffer Current	2.4	3.0		Volts	2,3,4
Vt +	Schmitt Trigger +Ve Threshold			1.7	1.9	Volts	2,3
Vt -	Schmitt Trigger -Ve Threshold		0.9	1.1		Volts	2,3

Note 1. These are normal Voltage and extended temperature specifications
Vdd from 3.0 V to 3.6 V
Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Refer to the CB35000 Standard Cell Specification for full Testing Levels and Conditions

Note 4. Buffers offered in 2, 4, 8, 12, 16, and 24 mA TTL options

Table 10 LVC MOS Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Vil	Low Level Input Voltage				0.2xVdd	Volts	2,3,4
Vih	High Level Input Voltage		0.8 x Vdd			Volts	2,3,4
Vol	Low Level Output Voltage	Iol = Rated Buffer Current		0.2	0.4	Volts	2,3,4,5,6
Voh	High Level Output Voltage	Ioh = Rated Buffer Current	0.85 x Vdd	0.9 x Vdd		Volts	2,3,4,5,6
Vt +	Schmitt Trigger +Ve Threshold			1.7	1.9	Volts	2,3
Vt -	Schmitt Trigger -Ve Threshold		0.9	1.1		Volts	2,3

Note 1. These are extended voltage and temperature specifications
Vdd from 2.7 V to 3.6 V
Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Refer to the CB35000 Standard Cell Specification for full Testing Levels and Conditions

Note 4. Buffers offered in 2, 4, and 8 mA CMOS options

Note 5. Note only one CMOS buffer may sink or source DC current when parametric measurements are taken due to the reason that the power supply specifications for CMOS product are not written to support DC current. If more than one buffer is active voltage drops in the supply may cause false failure readings.

Note 6. If no buffers are sinking or sourcing current and all internal pull up or pull down resistors in bidi buffers have been disabled by having the T2 Test Pin positive Vol (max) = 0.05 Volts and Voh (min)=Vdd-0.05 Volts

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Table 11 General Interface DC Electrical Characteristics (Note 1)

Symbol	Parameter	Conditions	Min	Typ	Max	Unit	Notes
Iil	Low Level Input Current	$V_i = V_{ss}$			+/-10	uA	2
Iih	High Level Input Current	$V_i = V_{dd}$			+/-10	uA	2
Ioz	Tri-State Output Leakage	$V_o = 0V$ or V_{dd}			+/-10	uA	2
Cin	Input Capacitance	Freq=1MHz		2.0	4.0	pF	3,4
Co	Output Capacitance	Freq=1MHz		4.0		pF	3,4
Cio	Bidi, I/O Capacitance	Freq=1MHz	0.9	1.1		pF	3,4
Ikl	I/O Latch Up Current	$V < V_{ss}$, $V > V_{dd}$	200	500		mA	
Vesd	Electrostatic Protection	HBM	2000	4000		V	5

Note 1. These are extended voltage and temperature specifications
Vdd from 2.7 V to 3.6 V
Temperature Ambient from -55 to 125 degrees Centigrade

Note 2. Adherence to rules in Power Pin / Pad Specifications Required

Note 3. Excluding Package

Note 4. At 0.0 Volts

Note 5. Human Body Model

CB35000 SERIES

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